



IN THE
UNITED STATES PATENT AND TRADEMARK OFFICE

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W. Chiang
G. Stanley
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APPLICANTS: Tony P. Chiang et al.
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FILING DATE: November 26, 2001
TITLE: Method for Integrated In-Situ Cleaning and Subsequent Atomic Layer Deposition Within a Single Processing Chamber
EXAMINER: David Nhu
GROUP ART UNIT: 2818
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LETTER TO THE CHIEF DRAFTSMAN

SIR:

Subject to the approval of the Primary Examiner in the above-entitled patent application, please substitute the formal drawing sheets containing Figures 1, 4A and 4B for the sheets containing Figures 1, 4A and 4B previously submitted.

Respectfully submitted,

Tony P. Chiang et al.

Dated: Sept. 26, 2002

By: 

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